Journal of Organometallic Chemistry, 84 (1975) 305-316 *0* **Elsebier Sequoia S.A., Lausanne - Printed in The Netherlands**

THE INFLUENCE OF OXYGEN ON THE DIRECT SYNTHESIS OF METHYLCHLOROSILANES

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Summary

'I'he influence of oxygen on the direct synthesis of methylchlorosilanes in a fluidised bed with copper as a catalyst has been studied. At 320° C and a pressure of 1 atmosphere the osygen content **in** the feed gas was varied from 1 to **5000** ppm- It was **found that the oxygen sharply reduces the rate of reaction** but hardly influences the product composition. The maximum degree of conversion of the silicon is about 70% if no oxygen is present; at an oxygen concentration of 2000 ppm the conversion decreases **LO 50 percent.**

Introduction

The direct (or Rochow) synthesis [1,2] is an important process for the production of methylchlorosilanes, the precursors of methylsi!icones. The synthesis is carried out commercially in a fluidised bed with silicon (purity > 98%), copper functioning as a catalyst. By adding promoters like zinc or antimony to the contact mixture the degree of selectivity to give the most desired product, dimethyldichlorosilane, reaches a value of about 90 mole percent. But for an economic production of silanes it is also necessary that the greatest possible percentage of the silicon introduced in the reactor be converted into silanes.

Because of the deactivation of the silicon-copper contact mixture this is only possible to a limited extent without formation of worthless by-products. On an industrial scale it is possible to convert 80-90 percent of the silicon into silanes [3]. In laboratory scale experiments on the direct synthesis usually no fresh contact mixture is supplied, and a decreasing reactivity and selectivity are observed when 40-70 percent of the silicon **has** been converted [4,5a].

Various factors affect the degree of usage of the silicon. During the synthesis a gradual deactivation of the contact misture surface occurs. This deactivation may be caused by a number of factors. For example, the deposition of carbon and carbonaceous products may block part of the surface [4,6]. Furthermore the activity can be decreased by a decreasing content of promoters on the contact mixture surface, e.g. as caused by the evaporation of $ZnCl₂$ [7a], by the accumulation in the reactor of elements present as contaminants in the silicon (for example iron), by the increase of free copper on the surface, causing enhanced **cracking, or by the blocking of the reactive** sites **by** reaction of the contact mixture with traces of oxygen, yielding silicon and copper oxides.

The poisoning of the contact mixture by oxygen was the subject of this investigation. It is known that even minor quantities of oxygen are detrimental to the synthesis of silanes [5b] but quantitative data are hardly known. Van Dalen investigated the direct synthesis both with methyl chloride freed from oxygen and with unpurified methyl chloride, containing at least 30 ppm osygen [7b]. No differences could be observed but a pulse of oxygen caused a temporary decrease in reactivity. Lobusevich et al. [8] stated that if 7400 ppm oxygen was added to the methyl chloride the reactivity decreased by 30 percent as compared to the reactivity when no oxygen is present; at the same time the selectivity to dimethyldichlorosilae decreased from 53 **to 46 percent.**

Experimental

TABLE 1

Type of experiments performed

in order to obtain information on the influence of oxygen a number of experiments were conducted $(21-210, \text{see Table 1});$ in these the oxygen con-

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centration in the feed gas was varied from 1 to 5000 ppm. Additional experiments (Zll, 212) were performed to investigate the influence of the oxygen concentration on the maximum degree of conversion of the **silicon.**

Apparatus

The experiments were carried out in the apparatus shown in Fig. 1. Methyl **chloride and nitrogen were supplied via flow meters and freed from oxygen and water by passage through a column containing active copper (BTS-catalyst,** type R 3-11, from BASF) and a column containing a 4A molecular sieve, **respectively. The oxygen concentration in the purified feed gas always amounted** to 0.5-5 ppm. The silanes and unconverted methyl chloride were partially separated by continuous distillation through a Vigreux column. The silanes and some of the methyl chloride were drained from the reboiler; the reflux was maintained by a Dewar vessel containing 15 kg of a CO₂/acetone mixture, which was sufficient to run the experiments for 18 h. The greater part of the unconverted methyl chloride was liquified in a second Dewar vessel (condenser) and stored in a container with vacuum wall. Uncondensable gases were discharged via an **eight-way valve and led off through a column containing KOH pellets to a gas meter. Oxygen could be injected in the feed gas through a calibrated stainless steel** capillary, situated after the BTS-catalyst and molecular sieve; the flow rate was calculated from the pressure drop across the capillary. The oxygen, injected

Fig. 1. Laboratory equpment for flud bed synlhesls. 1. Cyhnder unth mtrogen. 2. Cylmder untb methyl chloride. 3. BTS catalyst for oxygen removal. 4. Lmde molecular sieve 4A for water removal. 5. Magnetic valve. 6. Capillary for oxygen injection. 7. Flowmeter. 8. Hersch-cell. 9. Flow meter. 10. Fluid bed with **ailicoa 11. Reactor. 12. Dust trap contahing glass WOOL 13. DisciUation column. 14. Discharge of silnes.** 15. Dewar vessels with acetone/CO₂. 16, Vent. 17, Sample tube for gas analysis. 18, Dewar vessel for un**reacked methyl chloride 19. KOH pellets. 20. Gas meter. 21. Air for oxygen imectioa 22. Heatmg warer** for reboder. 23, Pressure air for fluid bed. $T =$ temperature: $P =$ pressure; $M =$ manometer.

Fig. 2. Hersch-cell apparatus for measunng the oxygen concentration.

as air, was previously dried by a molecular sieve. Before the reactor part of the gas mixture (30 ml/ruin) was passed through a Hersch-cell (Fig. 2, [9]j to measure the oxygen concentration continuously. The cell was calibrated by electrolysis of water (assuming 100% efficiency), thus adding a known amount of oxygen to a known amount of methyl chloride. Above 400 ppm measuring of the oxygen concentration by the Hersch-cell became difficult, and in this case **the** amount of oxygen was calculated from the known feed rate of the gases. At 400 ppm the calculated oxygen concentration was equal to the concentration as measured in the Hersch-cell.

The reactor (i-d. 28 and **length 600** mm, see Fig. 3) was made of glass and was situated in a fluidised bed containing silicon. The temperature in the synthesis reactor was kept constant to within **2°C by** control with a platinum resistance thermometer and was measured by chromel-alumel thermocouples.

Analysis of Reaction Products

The product mixture consisting of silanes and unconverted methyl chloride was analysed by means of gas-liquid chromatography with katharometer detection; separation took place on a 4 m copper column filled with nitrobenzene, 30% on Chromosorb W, at a temperature of 30°C. Hydrogen, dried on a molecular **sieve, was used as** *a* **carrier gas. The uncondensable gases were**

Fig. 3. Synthesis reactor for fluid bed experiments.

separated by gas-liquid chromatography with katharometer detection on a ²m stainless steel column filled with Linde molecular sieve 5.4; helium with 8.5% hydrogen was used as a carrier gas. In this way hydrogen, nitrogen, oxy gen and methane were separated; the uncondensable gases in the experiments consisted almost esclusively of methane (with nitrogen and oxygen if air had been added **to** the feed gas).

illaterials used

The silicon used in the experiments was technical silicon, the main impurities being 0.4% Fe, 0.1% Al and 0.3% Ca + Mg (by weight), and before use it was washed with water, dried, and treated with a magnet to remove part of the iron (resulting in an iron content of 0.2-0.3%). All esperiments were conducted in a fluidised bed, and because of this an easily fluidized mixture of silicon particles was used $[5c]$. Copper was introduced as pure copper chloride, prepared by a standard method $[5d]$ resulting in 10 wt % copper in the contact mixture. Pure zinc (0.1 wt %) and aluminium (0.05 wt %) were used as promoters. Methyl chloride, nitrogen and air were fed from cylinders.

Description of the experiments

Before each experiment the contact mixture was prepared in situ: silicon (91 g), CuCl, zinc and aluminium were stored in the reactor and dried at $100-$ 150°C for at least 3 h. Then the temperature was raised, and reaction between silicon and copper chloride took place between 250 and 300° C; when the re-

COhIPOSITION (in wt S) OF CONTACT MIXTURE AND DUST AFTER THE **E.XPERIMENTS**

c c.m. = contact mLxture.

212 58.3

action had ended the contact mivture was heated for about 16 h under a stream of purified nitrogen before starting the experiment.

0.0-l 1.2

0.4 1.0

0.9 1.5

3.7 0.23 6.8 1.-i

25.0 42

c.m _ dust

The experiments were conducted at temperatures between 315 and 340°C; reactivities were converted to a standard temperature of 320°C by use of the overall energy of activation of 26 kcal/mole. The product composition does not vary in this temperature region [5e]. More information of **the experiments is tabulated in Table 1; in this Table an oxygen concentration between 1 and 5 ppm indicates that no air was fed to the reactor. After each experiment the amount of carbon, hydrogen, copper, alurninium, zinc and iron were determined in the contact mixture and the entrained dust (see Table 2).**

Results and Discussion

The results of some experiments without supply of oxygen are shown m Fig. 4. The rate of reaction in the first part of the stable region of the synthe_

Fig. 4. Reactivity at 320°C as function of the silicon conversion; ppm O₂ = 1.

sis reaches a value between 80 and 110 g methyl chloride/kg Si/h at 320°C and the selectivity to dimethyldichlorosilane (D) a value of 90 mole percent. If methyl chloride with an oxygen concentration up to 1000 ppm is used no influence on the product composition is observed. The concentration of dimethyldichlorosilane remains at a constant level of 90 percent; the percentages of trichloromethylsilane (T) and trimethylchlorosilane (M) being 3-4 percent. The rate of reaction on the contrary, decreases very sharply between 1 and 1000 ppm oxygen and at 1000 ppm declines to a value of 65 percent of the value when no oxygen is present. When 350 ppm oxygen is fed to the reactor

Fig. 5. Product composition as function of the silicon conversion.

Fig. 6. Reactivity at 320°C as function of the silicon conversion.

the same degree of conversion of the silicon as in an oxygen free experiment can be reached (Fig. 8).

An oxygen concentration higher than 1000 ppm brings about a slight decrease in selectivity (25; Fig. 5); this decrease becomes greater as the oxygen content in the feed gas **increases** and amounts to 10 percent at 5000 ppm **oxygen. The** percentages **of** trichloromethylsilane and trimethylchlorosilane remain equal to each other, and reach higher values as the percentage of dimethyldichlorosilane decreases. When more than 1000 ppm oxygen is used the rate of reaction decreases less sharply than from 1 to 1000 ppm, as can **be seen in Fig. 9. If poisoning of the contact mixture is continued for some** hours the former level (no oxygen present) of selectivity is reached; the reaction rate on the other hand, remains low and does not reach the level of an oxygen-free experiment $(Z10; F_ic, 6)$. If 2000 ppm oxygen is present in the

Fig. 7. Product composition as function of the silicon conversion.

l.

Fig. 8. Reactivity at 320° C as function of the silicon conversion

feed gas the reaction rate remains very low (Fig. 8) and the selectivity starts decreasing at 35 percent conversion of the silicon; stopping the oxygen iniection does not restore the normal reactivity and selectivity (Fig. 7). A remarkable feature of the experiments is the constant rate of reaction **when** much oxygen was fed to the reactor.

The results of the experiments described above agree very well with the results obtained by Lobusevich et al.[8] with a contact mixture containing silicon, 10 percent copper and 0.005 percent **antimony. Lobusevich found** that adding 7400 ppm oxygen to the feed gas results in a decrease in selectivity of 14 percent; in the experiments described here the decrease at 5000 ppm amounted to 11 percent. Also the decrease in the reaction rate of 30 percent observed by Lobusevich agrees reasonably with the 50 percent decrease at 5000 ppm found in our experiments.

Kinetics

The kinetics of the direct synthesis of methylchlorosilanes in the pre**sence of oxygen can be analysed** with the **aid of these experiments if we as**sume that the fluidised bed reactor can be described as an ideal tubular re-

Fig. 9. Reactivity at 320°C as function of the oxygen concentration in the feed gas.

actor. It has **been demonstrated earlier [IO] that this is** indeed the case under the applied conditions. Further it is assumed that the influence of *osygen in* the temperature region of 315-340°C is the same for all temperatures (the adsorption equilibrium constant of oxygen on the contact mixture surface is assumed to be constant), and that minor changes in the product composition do not alter the overall kinetics.

During the synthesis, at constant oxygen feed rate, the equilibrium O_2 (g) = O_2 (ads) will be established in the reactor with the equilibrium constant $K_{\mathbf{O}_2} = R_{\mathbf{adsO}_2} (R_{\mathbf{desO}_2})^{-1}$. If both for methyl chloride and oxygen a Langmuir type adsorption is assumed, then for description of the synthesis four models must be considered; methyl chloride may adsorb via a single or dual site mechanism on the contact mixture surface $[7c, 5f]$ and also for oxygen one can assume the same possibilities; the overall rates of reaction for the four models can then be described by eqns. $1-4$:

$$
R = kK_m P_m [1 + K_m P_m + K_{02} P_{02} + K_p P_p]^{-1}
$$
 (1)

$$
R = kK_m P_m \left[1 + K_m P_m + (K_{O_2} P_{O_2})^{1/2} + K_p P_p\right]^{-1}
$$
 (2)

$$
R = kK_{\rm m}P_{\rm m} \left[1 + (K_{\rm m}P_{\rm m})^{1/2} + K_{\rm O_2}P_{\rm O_2} + K_{\rm p}P_{\rm p}\right]^{-2} \tag{3}
$$

$$
R = kK_m P_m \left[1 + (K_m P_m)^{1/2} + (K_{O_2} P_{O_2})^{1/2} + K_p P_p\right]^{-2}
$$
 (4)

 k = reaction velocity constant (g MeCl/kg Si/h);

 K = adsorption equilibrium constant; m = methyl chloride; O_2 = oxygen;

 $p =$ **p**roducts; $P =$ **pressure**;

TABLE 3

 R = reactivity at 320°C and 20% silicon conversion.

Because of the small conversion of methyl chloride during the experiments (see Table 3) the reactor can be considered as an ideal differential reactor with a constant pressure of methyl chloride; further, because of the small conversion, the concentration of products will not be very high and will not influence the synthesis $[11]$, so in eqns. 1-4 K_pP_p can be neglected. The average methyl chloride partial pressure in each experiment is given in Table 3; this

MAXIMUM METHYL CHLORIDE CONVERSIONS

 a_i ϵ = highest conversion of methyl chloride in reactor during experiment.

pressure has been corrected for the presence of oxygen and nitrogen and the conversion of methyl chloride; as can be seen from Table 3 one can assume an average partial pressure of methyl chloride of 0.97 atmosphere for all experiments.

Thus eqns. 1-4 may be simplified to:

$$
R^{-1} = C_1 + C_2 K_{02} P_{02}
$$
 (5)

$$
R^{-1} = C_3 + C_4(K_{O_2}P_{O_2})^{1/2}
$$
 (6)

$$
R^{-1/2} = C_5 + C_6 K_{O_2} P_{O_2}
$$
 (7)

$$
R^{-1/2} = C_7 + C_8(K_{O_2}P_{O_2})^{1/2}
$$
 (8)

with C, = constant.

If one of these equations applies, the esperimental results, piotted according to one of eqns. 5-8, should yield a straight line. The plots (Fig. 10) indicate clearly that only 6 and 8 fit the results in a **satisfactory manner. Further discrimination** between these two **models is not possible; the standard deviation for eqn. 6 amounr,s to 8.27 and for eqn. 8 to SO0 g MeCl/kg Si/h. In Fig. 9 the**

Fig. 10 Testmg oi models. a. eqn 5; b. eqn. 6; c. eqn 7; d, eqn 8.

$$
R = [0.01064 + 0.21253(P_{O_2})^{1/2}]^{-1}
$$

with 0.01064 = (1 + $K_m P_m$)($kK_m P_m$)⁻¹
0.21253 = $(K_{O_2})^{1/2} (kK_m P_m)^{-1}$ (P_m = 0.97 atm)

The constants in this equation were determined by means of the method of least squares. Assuming $K_m = 0.029$ atm⁻¹ [7c] it follows that K_{0} , = 421 **atm-' .** The results obtained in our esperiments agree qualitatively very well with the results obtained by Meyer and Vrakking on the adsorption of osygen on a clean silicon surface $[12]$. A very stable surface species upon $0₂$ adsorption, eshibiting oxide structure, has been found in their investigations.

Conclusions

In the direct synthesis of methylchlorosilanes with copper as a catalyst and zinc and aluminium as promoters the selectivity to dimethyldichlorosilane is only slightly dependent on the oxygen concentration in the range of l-5000 ppm $O₂$. The decrease in selectivity becomes greater as the amount of oxygen increases and amounts to 11 percent at 5000 ppm. The reactivity is strongly dependent on the oxygen concentration and decreases between 1 and 5000 ppm by a factor 2. Also the maximum conversion of the silicon is strongly dependent on the oxygen concentration and decreases as the concentration of oxygen increases.

The **influence of oxygen 011 the direct synthesis can be described by a** Langmuir type dual site adsorption of oxygen on the contact mi.ture surface. The very hign adsorption equilibrium constant results in a high coverage of the surface, so the reaction rate decreases sharply when even only small quantities of oxygen are present. Another possibility for the poisoning effect of oxygen is the reaction with hydrogen (always present in small quantities due to the cracking of methyl chloride) to form $H₂O$, as proposed by Lobusevich et al.

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